Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

- 1 (Cancelled):
- 2 (Currently Amended): An exposure apparatus according to claim 1, comprising:

 a projection optical system for projecting a pattern of a mask onto a substrate; and
 a fluid supply unit for supplying a fluid between said projection optical system
 and the substrate, said fluid supply unit including an injection unit for injecting carbon dioxide
 into the fluid.

wherein said fluid supply unit includes a degassing unit for degassing the fluid, said degassing unit being located at an upstream side of the injection unit.

3(Currently Amended): An exposure apparatus according to claim [[1]] 2, wherein said injection apparatus includes a membrane module for injecting the carbon dioxide.

- 4 (Currently Amended): An exposure apparatus according to claim [[1]] 2, wherein the injection unit injects the carbon dioxide at a concentration of the carbon dioxide in the fluid between 0.02 ppm and 750 ppm.
- 5 (Original): An exposure apparatus according to claim 4, wherein the injection unit injects the carbon dioxide at the concentration of the carbon dioxide in the fluid between 0.06 ppm and 300 ppm.

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6 (Currently Amended): An exposure apparatus according to claim [[1]] 2, wherein the

fluid supply unit includes a resistivity meter for measuring a resistivity value of the fluid, and the

injection unit injects the carbon dioxide based on a measurement result of the resistivity meter.

7 (Currently Amended): An exposure apparatus according to claim [[1]] 2, wherein the

injection unit injects the carbon dioxide so that a resistivity value of the fluid is between $0.02\,$

MΩ·cm and 10 MΩ·cm.

8 (Original): An exposure apparatus according to claim 7, wherein the injection unit injects the

carbon dioxide so that the resistivity value of the fluid is between 0.04 M Ω ·cm and 5 M Ω ·cm.

9-12 (Cancelled):

13(Currently Amended): A device manufacturing method comprising the steps of:

exposing an object using an exposure apparatus according to claim [[1]] 2 and

developing the exposed object.

14-23 (Canceled):

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